



**University of Hawaii,
Bruker and Renishaw present
Advanced AFM and AFM-Raman Workshop**



AFM has been used for many years for ultra high-resolution microscopy and has earned a reputation as a powerful but complex tool. Recent advances by Bruker are making AFM easier to use, providing more unambiguous and quantitative information, and extending the ability of AFM to provide Nanoscale Chemical-ID information in addition to quantitative adhesion, modulus and mechanical property while working with the most challenging samples. These advances include **ScanAsyst** mode, **PeakForce QNM** and **IRIS – integrated AFM Raman Imaging System**.

Thursday July 12 - 10:30am - 12 pm:

Technical Talks:

- 1. AFM Imaging – Beyond Topography
-Mayur Savla, Bruker Nano Inc.**
- 2. Raman-AFM: towards nanoscale chemical
and structural imaging -Dr. Andrew King,
Renishaw Inc., Spectroscopy Product Division**

Thursday July 12 - 9:00am - 4pm:

Multimode-8 demo & imaging customer samples

Location: Holmes Hall, Rm # 389

Registration and more information:

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